

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: Ogata et al.

Examiner: Lee, Sin J

Application No.: 10/589,382

Group Art Unit: 1795

Filed: August 15, 2006

Docket: 1608-6 PCT/US

For: **PHOTORESIST COMPOSITION  
AND METHOD OF FORMING RESIST  
PATTERN**

Dated: January 26, 2009

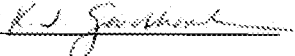
Confirmation No.: 6030

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Dated: January 26, 2009

Signature: K.J. Goodhand: 

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE TO OFFICE ACTION UNDER 37 C.F.R. §1.111**

Sir:

In response to the final Office Action dated October 30, 2008, the due date for which is January 30, 2009, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 5 of this paper.

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